

# Etch / Develop / Clean

Ideal for solvent-, acid-, and aqueous-based applications



EDC1-100-8NPP SHOWN

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TECHNOLOGIES CORPORATION

# Our most versatile system ever!

## Features

- Substrate capabilities: from small fragments to 200mm wafer or 7" (178mm) square
- Digital Process Controller—programmable speed, valve action and time (twenty 51-step programs or manual mode)
- Solid Natural Polypropylene or Teflon® housing with interlocking upper plenum
- Clear ECTFE domed lid with adjustable injectors
- Teflon® control valves with single fan-spray injector for a sequential dry-wet-dry process
- Adjustable process N2 diffuser with Teflon® control valve (top center in lid)
- A wide variety of non-vacuum edge-grip chucks to choose from. No vacuum is required! (Choose EDC2 for vacuum chuck)
- Optional: Simultaneous front- and back-side process capability (call factory)
- Drain and exhaust port (drain tubing and exhaust duct are included)
- Electrically double insulated and overload protected
- Safety door interlock (prevents rotation, as well as dispense, when lid is open and locks chamber during process)

## Typical Processes Supported

Rinse-Dry  
Etch-Rinse-Dry  
Develop-Rinse-Dry  
Solvent-based Cleaning  
Aqueous-based Cleaning

**E**etch  
**D**velop  
**C**lean

This product is not intended for automatic loading or integration into robotic systems

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441 Industrial Drive North Wales, PA 19454  
TEL: 215-699-7278 FAX: 215-699-4311  
<http://www.laurell.com>  
[sales@laurell.com](mailto:sales@laurell.com)